# Bulk doping effects in hybrid organic/ inorganic systems from quantum mechanical first principles 

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$$
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$$



# Organic Electronics - Plastic Electronics 


sources (left to right): Organic Electronic Association, Eco Friend, Nature Publishing Group, Samsung

## Organic Electronics - Plastic Electronics




Inorganic/organic interfaces are already present...
... and affect or determine device properties.
Can we understand and control them?


## Hybrid Inorganic/Organic Interfaces (HIOS)

## Combine the best of two worlds...

## Hybrid electronics:

- make interface central

$\mathrm{ZnO} / \mathrm{p}$-sexiphenyl (courtesy of S. Blumstengel)


## Potential for new physics at HIOS

solid


- potential for new interface morphologies


## HIOS in reality - defects and disorder

solid
 defects...


disorder...
organic


HIOS

## Optimizing HIOS - the right combination



- What is the right combination?
- Vast chemical compound space



## Fundamental questions at HIOS interfaces



- What is the nature of charge carriers?
- Do new quasiparticles emerge at interface?


## Atomistic understanding of molecules@surfaces

## Charge transfer

Level alignment

Van der Waals interaction

Surface structure
Adsorption geometry

## Atomistic understanding of molecules@surfaces

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## Level alignment

Van der Waals interaction

Surface structure
Adsorption geometry

## Level alignment at interface


injection limited current:

$$
j \propto A T^{2} \exp \left(-\frac{\text { charge injection barrier }}{k_{B} T}\right)
$$

## Modifying level alignment at interface


interface layer to adjust level alignment

## Modifying level alignment at interface



## Charge transfer induced work function increase

High doping $\Rightarrow$ flat bands $\Rightarrow$ metallic regime
vacuum level

molecular
acceptor
state


## Charge transfer induced work function increase

High doping $\Rightarrow$ flat bands $\Rightarrow$ metallic regime


## Formation of space-charge layer

low doping $\Rightarrow$ band bending


## Quantum mechanical treatment

## adsorption energy:



## Our Code: FHI-aims [1]

All-electron DFT and beyond code developed in the Fritz-Haber-Institut

- Accurate numerical atomic orbital basis sets:

$$
\varphi_{i}(\vec{r})=\frac{u_{i}(r)}{r} Y_{l m}(\Omega)
$$

- Massively scalable, massively parrallel
- DFT functionals: LDA, PBE, hybrids (HSE), ...
- pairwise van der Waals (vdW) scheme [2]:



## Adsorption geometries and energies

$$
E^{a d s}=E^{\text {mol@surf }}-E^{m o l}-E^{s u r f}
$$

F4TCNQ on hydrogen terminated $\mathbf{Z n O}(000-I)$


> upright
$E^{a d s}=0.40 \mathrm{eV}$

- $\mathbf{Z n}$
- $\mathbf{O}$

$E^{a d s}=1.84 \mathrm{eV}$
flat-lying
all energies: $\mathrm{HSE}^{*}+\mathrm{vd} W^{\text {scr }}$




## Adsorption geometries and energies

$$
E^{a d s}=E^{m o l @ s u r f}-E^{m o l}-E^{s u r f}
$$

F4TCNQ on hydrogen terminated $\mathrm{ZnO}(000-\mathrm{I})$


## upright

 $E^{a d s}=0.40 \mathrm{eV}$ - ZnStructural features:

- weak binding (hydrogen bonding, vdW)
- CN groups bind to hydrogens
- F4TCNQ does not bend appreciably all ene (unlike on metals)


## Adsorption geometries and energies



## F4TCNQ@ZnO in DFT

Our normal DFT calculations: undoped
vacuum level
 function change

F4TCNQ
LUMO
no work


## F4TCNQ@ZnO in DFT

Our normal DFT calculations: undoped


## Step 1: add electrons to DFT calculation

 adsorption energy:

$$
E^{a d s}(q)=E^{m o l @ \operatorname{surf}}(q)-E^{m o l}-E^{s u r f}+q \Delta \epsilon_{F}
$$

## Adding electrons to surface calculations

## adsorption energy:

$$
E^{a d s}=E^{m o l @ s u r f}-E^{m o l}-E^{s u r f}+q \mu_{e}
$$

chemical potential of electrons

## Adding electrons to surface calculations

## adsorption energy:

$$
E^{\text {ads }}=E^{\text {mol@surf }}-E^{\text {mol }}-E^{\text {surf }}+q \mu_{e}
$$

Adding electrons to supercells: chemical potential of electrons

- requires compensating charge background

supercell


## Adding electrons to surface calculations

## adsorption energy:

$$
E^{\text {ads }}=E^{\text {mol@surf }}-E^{\text {mol }}-E^{\text {surf }}+q \mu_{e}
$$

Adding electrons to supercells:
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## Adding electrons to surface calculations

## adsorption energy:

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Adding electrons to supercells: chemical potential of electrons

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supercell


## Adding electrons to surface calculations

## adsorption energy:

$$
E^{a d s}=E^{m o l @ s u r f}-E^{m o l}-E^{s u r f}+q \mu_{e}
$$

Adding electrons to supercells:
chemical potential of electrons

- we confine charge background (virtual crystal approximation)


In our all-electron code:

- we change nuclear charge:

$$
Z \rightarrow Z+\delta \quad\left(\delta \sim 10^{-2}\right)
$$

supercell

## Adsorption energy as function of Fermi energy



## Step 2: contribution from space charge region

Step 2a:
bulk doping concentration

- translate Fermi energy into doping dependence (standard semiconductor text book expressions)

$$
\Delta \epsilon_{\mathrm{F}} \rightarrow N_{D}
$$

Step 2b:

- introduce space charge region (add band bending contribution)
surface area supercell length
$\Delta E_{q}^{\mathrm{ads}}\left(N_{\mathrm{D}}\right)=E_{\mathrm{ads}}^{\mathrm{DFT}}(q)-\underbrace{\frac{e^{2} \downarrow}{6 \varepsilon \varepsilon_{0} N_{\mathrm{D}} A^{2}}|q|^{3}}+\underbrace{\frac{e^{2} d^{\swarrow}}{6 \varepsilon \varepsilon_{0} A} q^{2}}$
macroscopic band bending
spurious band bending
in calculation


## Step 2: contribution from space charge region

Step 2a:
bulk doping concentration

- translate Fermi energy into doping dependence (standard semiconductor text book expressions)

$$
\Delta \epsilon_{\mathrm{F}} \rightarrow N_{D}
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Step 2b:

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Step 2c:
- maximize $\Delta E_{q}^{\text {ads }}\left(N_{\mathrm{D}}\right)$ for optimal charge transfer $Q$


## Introducing bulk doping into 1st principles

$$
E^{a d s}\left(N_{D}\right)=\underbrace{E^{\text {mol@surf }}-E^{\text {mol }}-E^{\text {surf }}}+\underbrace{\Delta_{B B}\left(Q, N_{D}\right)}
$$ microscopic: DFT macroscopic model

charge transfer

adsorption energy

Y. Xu, O.T. Hofmann, R. Schlesinger, S.Winkler, J. Frisch, J. Niederhausen, A.Vollmer, S. Blumstengel, F. Henneberger, N. Koch, P. Rinke, and M. Scheffler, submitted to Phys. Rev. Lett

## Introducing bulk doping into 1st principles

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$$ microscopic: DFT macroscopic model



## Adsorption energy and charge transfer

- large work function increase




## Formation of space-charge layer

low doping + deep donors $\Rightarrow$ band bending pins


## Work function increase in photoemission

photoemission (UPS/XPS) in collaboration with:

## Humboldt University Berlin

R. Schlesinger
J. Frisch
J. Niederhausen
S. Blumstengel
F. Henneberger
N. Koch

Synchrotron BESSY II
S.Winkler
A.Vollmer


## Experiment

- work function increase: 1.4 eV
- minimal charge transfer


Collaborative Research Center "Hybrid Inorganic/ Organic Systems" F. Henneberger, P. Rinke, M. Scheffler, and N. Koch, Phys. Rev. B 87, I553II (2013)

## F4TCNQ@ZnO - photoemission

F4TCNQ@ZnO(00-I0)
 similar spectra for $\mathrm{ZnO}(0010)$

## F4TCNQ@ZnO - photoemission

F4TCNQ@ZnO(00-10)

R. Schlesinger, et al., Phys. Rev. B 87, I553II (2013)

## F4TCNQ@ZnO - photoemission



- extraordinarily large work function changes
R. Schlesinger, et al., Phys. Rev. B 87, I553II (2013)


## Workfunction of F4TCNQ@ZNO



- DFT-HSE workfunction in good agreement with UPS


## Workfunction of F4TCNQ@ZNO



## H-deficient $\mathbf{Z n O}-\mathrm{O} \mathbf{2 x 1}-\mathrm{H}$ surface

O dangling bond


## H-deficient $\mathbf{Z n O - O} \mathbf{2 x 1}-\mathrm{H}$ surface



## H-deficient $\mathbf{Z n O}-\mathbf{O} \mathbf{2 x 1}-\mathrm{H}$ surface



## $\mathrm{ZnO}-\mathrm{O}$ in contact with H -reservoir

- H-deficient surfaces stabilized by n-type conditions

N. Moll,Y. Xu, O. Hofmann, P. Rinke, New J. Phys. in press


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## Experimental evidence



|  | surf. core <br> level shift |
| :---: | :---: |
| Exp. | 2.0 eV |
| DFT | 2.3 eV |

peak weights:

- H-coverage ~30-40\%

PBE $\Delta$ self-consistent field (SCF) calculations reveal:

- only H-terminated structures match exp. core level shifts


## HIOS are fascinating systems

## Charge transfer

## Level alignment

Surface structure

Van der Waals interaction

Adsorption geometry
Defects


## Atomistic understanding of HIOS

## Charge transfer

## Level alignment

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Surface structure

## Atomistic understanding of molecules@surfaces

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N. Koch
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S.Winkler
A.Vollmer


## Adsorption geometries and energies



- monolayer is composed of flat-lying molecules
- molecular orientation in layer random: disorder (no impact on electronic structure)


## Step 2: contribution from space charge region

Step 2a:
bulk doping concentration

- translate Fermi energy into doping dependence (standard semiconductor text book expressions)

$$
\Delta \epsilon_{\mathrm{F}} \rightarrow N_{D}
$$

$$
\frac{N_{\mathrm{D}}}{1+2 \exp \left(\frac{\Delta \epsilon_{\mathrm{F}}}{k_{\mathrm{B}} T}\right) \exp \left(\frac{E_{\mathrm{d}}}{k_{\mathrm{B}} T}\right)}=N_{\mathrm{C}} \frac{2}{\sqrt{\pi}} F_{1 / 2}\left(\frac{\Delta \epsilon_{\mathrm{F}}}{k_{\mathrm{B}} T}\right)
$$

donor binding energy
( 30 meV )

$$
\begin{gathered}
N_{\mathrm{C}}=2\left(\frac{2 \pi m^{*} k_{\mathrm{B}} T}{h^{2}}\right)^{\frac{3}{2}} \\
F_{1 / 2}\left(\eta_{\mathrm{F}}\right)=\int_{0}^{\infty} \frac{\eta^{1 / 2} \mathrm{~d} \eta}{1+\exp \left(\eta-\eta_{\mathrm{F}}\right)}
\end{gathered}
$$

## F4TCNQ@ZnO schematically

low doping + deep donors $\Rightarrow$ band bending pins


## F4TCNQ@ZnO schematically

$$
\Delta \Phi=\Delta \Phi_{\mathrm{ID}}+\Delta \Phi_{\mathrm{BB}}=\frac{\delta q}{\varepsilon_{0}} d_{e f f}+\frac{\delta q^{2}}{2 \varepsilon_{0} \varepsilon N_{D}}
$$


R. Schlesinger, et al., Phys. Rev. B 87, I553II (2013)

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R. Schlesinger, et al., Phys. Rev. B 87, I553II (2013)

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